

Bruce Oxidation/Diffusion Furnace



The Bruker Oxidation Furnace features 3 zone tubes that can be used to grow wet and dry oxides as well as perform drive-in/annealing for elevated temperature device processing. The system features two working tube. Tube 1 is used for the oxidation of **bare silicon wafers only** while tube 2 can be used for processes involving other types of wafers. After passing the NCF safety exam, users can request training on this machine by sending an email to ncftech@uic.edu. Those not trained can request an NCF work service order by contacting the lab manager.

Location: cleanroom, deposition bay

Training: 3 sessions (2 trainings and a checkout session)

Technical Specifications:

- # of Temp Zones: 3 temperature zones per tube
- Temp Deviation: < 2 °C per zone
- Wafer sizes: 2, 3, and 4-inch
- Gases: N_2 (with bubbler), O_2
- Boats: Various quartz boats available